



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Krahmer et al.  
Serial No. : 10/817,527  
Filed : April 1, 2004  
Title : OBJECTIVE WITH FLUORIDE CRYSTAL LENSES  
Art Unit : Unknown  
Examiner : Unknown

**MAIL STOP AMENDMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Applicants request consideration of the references listed on the attached PTO-1449 form. Under 37 C.F.R. § 1.98 (a)(2)(ii), only copies of foreign patent documents and/or non-patent literature are enclosed. Copies of any listed U.S. patents or U.S. patent application publications can be provided upon request.

This statement is being filed within three months of the filing date of the application or before the receipt of a first Office Action on the merits. Please apply any charges or credits to Deposit Account No. 06-1050.

Respectfully submitted,

Date: 12/19/08

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CERTIFICATE OF MAILING BY FIRST CLASS MAIL

I hereby certify under 37 CFR §1.8(a) that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage on the date indicated below and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

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Substitute Form PTO-1449  
(Modified)U.S. Department of Commerce  
Patent and Trademark OfficeAttorney's Docket No.  
17979-006002Application No.  
10/817,527**Information Disclosure Statement  
by Applicant**

(Use several sheets if necessary)

(37 CFR §1.93(b))

Applicant  
Krahmer et al.Filing Date  
April 1, 2004

Group Art Unit

**U.S. Patent Documents**

| Examiner Initial | Desig. ID | Document Number | Publication Date | Patentee | Class | Subclass | Filing Date If Appropriate |
|------------------|-----------|-----------------|------------------|----------|-------|----------|----------------------------|
|                  | AA        | 6,785,051       | 8/31/04          | Allan    |       |          |                            |

**Foreign Patent Documents or Published Foreign Patent Applications**

| Examiner Initial | Desig. ID | Document Number                               | Publication Date | Country or Patent Office | Class | Subclass | Translation |    |
|------------------|-----------|---|------------------|--------------------------|-------|----------|-------------|----|
|                  |           |   |                  |                          |       |          | Yes         | No |
|                  | AB        | WO 01/50171<br>(translation of abstract only) | 07/12/01         | WIPO                     |       |          | X           |    |

**Other Documents (include Author, Title, Date, and Place of Publication)**

| Examiner Initial | Desig. ID | Document   |
|------------------|-----------|--|
|                  | AC        | Wang et al. "Polarized Phase Shift Mask: Concept, Design, and Potential Advantages to Photolithography Process and Physical Design." Proceedings of SPIE vol. 4562, 21st Annual BACUS Symposium on Photomask Technology, March 2002, p. 406-417. |
|                  | AD        | Hodgkinson, Ian. "Review of birefringent and chiral optical interference coatings." Optical Interference Coatings, Trends in Optics and Photonics vol. 63, 2001, p. FA1-FA3.   |
|                  | AE        | Band, Erster. Lexikon der Optik. 1999, p. 380-387. and certified copy of translation.  |
|                  | AF        | Burnett et al. "The Trouble with Calcium Fluoride." SPIE's OEMagazine, pp. 23-25, March 2002.  |
|                  | AG        | Matsuyama et al. "High NA and low residual aberration projection lens for DUV scanner." Optical Microlithography XV, Proceedings of SPIE, 4691, pp. 687-695, 2002.   |
|                  | AH        | Matsuyama et al. "Microlithographic lens for DUV scanner." International Optical Design Conference, Proceedings of SPIE 4832, pp. 170174, 2002.  |
|                  | AI        | Matsumoto, et al. "Analysis of Imaging Performance Degradation." Optical Microlithography XVI, Proceedings of SPIE, 5040, pp. 131-138, 2003.   |
|                  | AJ        | Owa et al. "Nikon F2 exposure tool development." Optical Microlithography XVI, Proceedings of SPIE, 5040, pp. 772-780, 2003.   |
|                  | AK        | Chiba et al. "New generation projection optics for ArF lithography." Optical Microlithography XVI, Proceedings of SPIE, 4691, pp. 679686, 2002.  |

Examiner Signature

Date Considered

EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.